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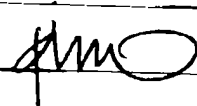
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**FACSIMILE COVER SHEET**

TO: Examiner Zarneke  
FROM: David E. A. Jordan, Reg. No. 50,325  
RE: U.S. Patent Application No. 09/867,611  
Our Ref.: 03560.002364.1  
FAX NO.: (703) 308-7722  
DATE: May 27, 2003 NO. OF PAGES: 5  
(including cover page)  
TIME: 4:10 SENT BY: 

**MESSAGE**

Examiner Zarneke:

Attached is a proposed claim sheet in advance of our personal interview, scheduled for May 29, 2003 at 2:30 p.m.

In the interview, I intend to discuss how there is no motivation to combine U.S. Patent No. 5,959,638 (Konuma) with allegedly admitted prior art.

David E. A. Jordan

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Docket No. 03560.002364.1  
Application No. 09/867,611

**PROPOSED CLAIM SHEET - DO NOT ENTER**

26. to 36. (Allowed)

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37. (Proposed) A process of producing a nanostructure comprising an anodized film including a plurality of nanoholes on a substrate, said process comprising the steps of:

- (i) preparing a film including aluminum on the substrate; and
- (ii) anodizing the film,

wherein in step (ii) the anodizing includes a first process in which an anodization current is a steady value and a second process in which the anodization current decreases after said first process, and

wherein said first process and said second process occur consecutively, and

wherein each of said plurality of nanoholes has a uniform shape.

38. (Proposed) A process for producing a nanostructure comprising an anodized film including a plurality of nanoholes on a substrate, said process comprising steps of:

- (i) preparing a film including aluminum on the substrate which has a surface containing at least one material selected from the group consisting of semiconductors, noble metals, Mn, Fe, Co, Ni, Cu and carbon; and

(ii) anodizing the film,

wherein in step (ii) the anodizing includes a first process in which an anodization current is a steady value and a second process in which the anodization current decreases after said first process, ~~and~~

wherein said first process and said second process occur consecutively, and

wherein each of said plurality of nanoholes has a uniform shape.

39. (Previously Added) A process for producing a nanostructure according to Claim 37, wherein the anodizing terminates after the anodization current is decreased from a steady value to 95% or below of the steady value.

40. (Previously Added) A process for producing a nanostructure according to Claim 37, wherein the anodization current returns to the steady value after said second process, and wherein the anodizing terminates by the time the anodization current reaches the steady value after said second process.

41. (Previously Added) A process for producing a nanostructure according to Claim 37, wherein the nanohole passes through the anodized film from the surface of the anodized film to the surface of the substrate.

42. (Previously Added) A process for producing a nanostructure according to Claim 39, wherein a process for enlarging a diameter of the nanohole is performed after step (ii).

43. (Previously Added) A process for producing a nanostructure according to Claim 37, wherein the surface of the substrate on the side of the film has a first region having first electrical resistivity and a second region having second electrical resistivity that is different from the first electrical resistivity.
44. (Previously Added) A process of producing a nanostructure according to Claim 37, wherein the surface of the substrate on the side of the film has a first region having first electrical resistivity and a second region having second electrical resistivity that is different from the first electrical resistivity, and the nanohole is on the second region and does not pass through the anodization film from the surface of the anodized film to the surface of the substrate.
45. (Previously Added) A process for producing a nanostructure according to Claim 37, wherein a process for forming recessed portions on the film is performed before step (ii).
46. (Previously Added) A process for producing a nanostructure according to Claim 37, wherein a process for growing a carbon nanotube in the nanohole is performed after step (ii).
47. (Previously Added) A process for producing a nanostructure according to Claim 38, wherein the anodizing terminates after the anodization current is decreased from a steady value to 95% or below of the steady value.

48. (Previously Added) A process for producing a nanostructure according to Claim 38, wherein the anodization current returns to the steady value after said second process, and wherein the anodizing terminates by the time the anodization current reaches the steady value after said second process.

49. (Previously Added) A process for producing a nanostructure according to Claim 38, wherein the nanohole passes through the anodized film from the surface of the anodized film to the surface of the substrate.

50. (Previously Added) A process for producing a nanostructure according to Claim 47, wherein a process for enlarging a diameter of the nanohole is performed after step(ii)

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